

REMARKS

Claims 1-11, 15-17, 30, 32-35, 37-44, 48-69, 73-80 and 83-85 now remain in this application. Claims 12-14, 18-29, 31, 36, 45-47, 70-72 and 81-82 have been withdrawn.

Claims 1-85 were subject to restriction and/or election requirement.

Election/Restrictions

The claims were held to be directed to the following four sets of species:

A.) RF biasing techniques:

- i) pulse modulation bias techniques;
- ii) single burst bias;

and

B.) Workpiece or substrate or type of layer treated:

- i) dielectric;
- ii) semiconductor;

and

C.) Pre-treatments:

- i) passivation of workpiece;
- ii) "pre-cleaning" of workpiece;
- iii) plasma cleaning chamber;

and

D.) Post-treatments:

- i) thermal annealing;
- ii) stripping photoresist or mask;
- iii) wet-cleaning.

The applicants were required to elect a single disclosed species from each of the four sets of species groups, i.e., one from each of Groups A, B, C and D, for prosecution.

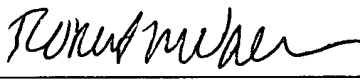
Therefore, applicants hereby elect Species ii of Group A

(single burst bias), Species ii of Group B (semiconductor layer), Species i of Group C (passivation), and Species i of Group D (annealing). **The claims reading on these elected species include Claims 1-11, 15-17, 30, 32-35, 37-44, 48-69, 73-80 and 83-85.** Claims 12-14, 18-29, 31, 36, 45-47, 70-72 and 81-82 are withdrawn, for later consideration should a generic claim be allowed.

As for Group A, this election includes claims that read on a continuous RF bias. As for Group B, this election includes claims that read on implantation in a semiconductor material of a workpiece that also includes a dielectric layer or layers. As for Group C, the passivation referred in Claim 15) pertains to passivation of the chamber.

Respectfully submitted,

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